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APPLICATION NO. FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
10/608,406	06/26/2003	Mohamad Shaheen	42P16009	8443		
7590 06/08/2005			EXAMINER			
Lester J. Vincent			LOKE, STEVEN HO YIN			
	KOLOFF, TAYLOR & 2	ZAFMAN LLP		 		
Seventh Floor		ART UNIT	PAPER NUMBER			
12400 Wilshire	Boulevard	2811				
Los Angeles, C.	A 90025					
			DATE MAILED: 06/08/2009	DATE MAILED: 06/08/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Applica	ation No.	Applicant(s)	600			
Office Action Summary		10/608	,406	SHAHEEN ET AL.	(Bus			
		Examin	er	Art Unit				
		Steven		2811				
The Period for Re	MAILING DATE of this community	nication appears on t	the cover sheet with the c	correspondence addre	ess			
THE MAIL - Extensions after SIX (6) - If the period - If NO period - Failure to re Any reply re	ENED STATUTORY PERIOD F ING DATE OF THIS COMMUN of time may be available under the provision: MONTHS from the mailing date of this comfor reply specified above is less than thirty (if for reply is specified above, the maximum sply within the set or extended period for reply ceived by the Office later than three months int term adjustment. See 37 CFR 1.704(b).	ICATION. s of 37 CFR 1.136(a). In no munication. 30) days, a reply within the statutory period will apply and y will, by statute, cause the a	event, however, may a reply be tin statutory minimum of thirty (30) day I will expire SIX (6) MONTHS from application to become ABANDONE	nely filed s will be considered timely. the mailing date of this comm D (35 U.S.C. § 133).	nunication.			
Status				•				
1)⊠ Res	consive to communication(s) fil	ed on <i>28 March 200</i>	95 .					
·	` · ·	2b)⊠ This action is						
•	, —·							
Disposition o	f Claims							
4a) 0 5)	m(s) <u>1,2 and 4-8</u> is/are pending of the above claim(s) is/a m(s) is/are allowed. m(s) <u>1,2 and 4-6</u> is/are rejected m(s) <u>7, 8</u> is/are objected to. m(s) are subject to restri	are withdrawn from o						
Application P	apers							
9)	specification is objected to by th	ne Examiner.						
10) <u></u> The	drawing(s) filed on is/are	: a) accepted or	b) ☐ objected to by the	Examiner.				
* *	icant may not request that any obje	•	· ·					
	acement drawing sheet(s) includin oath or declaration is objected t	•		-				
Priority unde	r 35 U.S.C. § 119							
a)	Certified copies of the priority	documents have be documents have be of the priority documents Bureau (PCT F	een received. een received in Applicat ments have been receive Rule 17.2(a)).	ion No ed in this National St	age			
Attachment(s)								
	eferences Cited (PTO-892) raftsperson's Patent Drawing Review (PTO 048\	4) Interview Summary Paper No(s)/Mail D					
3) Information	Disclosure Statement(s) (PTO-1449 o)/Mail Date			Patent Application (PTO-1	52)			

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1. Claims 1 and 4 are objected to because of the following informalities: Claim 1, line 9, the phrases "439C" and "451C" are unclear whether they are being referred to "439 degrees C" and "451 degrees C", respectively. Claim 4, line 2, the phrases "419C" and "430C" are unclear whether they are being referred to "419 degrees C" and "430 degrees C". Appropriate correction is required.

2. Claims 4 and 5 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claim 1, the parent claim of claim 4, discloses the first annealing temperature is between approximately 439 degrees C and approximately 451 degrees C. However, it is unclear why claim 4 discloses the first annealing temperature is between approximately 419 degrees C and approximately 430 degrees C. The first annealing temperature of claim 4 is outside the range of the annealing temperature of claim 1. The annealing temperature of claim 1 is used for the thermal cleave operation for the wafer separation while the annealing temperature of claim 4 is used for the mechanical cleave operation for the wafer separation (paragraph [0029] of applicant's specification). It is believed that claim 4 should not depend upon claim 1.

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States

only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

4. Claims 1, 2 and 6 are rejected under 35 U.S.C. 102(e) as being clearly anticipated by Bryan.

In regards to claim 1, Bryan shows all the elements of the claimed invention in figs.

1-6. It is an integrated circuit (col. 1, lines 8-19), comprising: a semiconductor substrate [31]; a device layer [19] coupled to the substrate, the device layer having been coupled to the substrate via a transfer process comprising: doping the device layer with a first quantity of a first ionic material [17] (silicon) and a second quantity of a second ionic material [22] (hydrogen); annealing (heating) (col. 5, lines 44-54, col. 6, lines 1-5) the device layer and semiconductor substrate at a first annealing temperature.

In regards to claim 1, the process limitation of how the device layer is formed has no patentable weight in claim drawn to structure. Note that a product by process claim is directed to the product per se, no matter how actually made, In re Hirao, 190 USPQ 15 at 17 (footnote 3). See also In re Brown, 173 USPQ 685; In re Luck, 177 USPQ 523; In re Fessmann, 180 USPQ 324; In re Avery, 186 USPQ 161; In re Wertheim, 191 USPQ 90 (209 USPQ 554 does not deal with this issue); and In re Marosi et al, 218 USPQ 289, all of which make it clear that it is the patentability of the final product per se which must be determined in a product by process claim, and not the patentability of the process, and that an old or obvious product by a new method is not patentable as a product, whether claimed in product by process claims or not. Note that applicant has the burden of proof in such cases, as the above caselaw makes clear.

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Therefore, the phrase "epitaxial layer", the phrase "a transfer process", and the phrase "annealing the epitaxial layer and semiconductor substrate at a first annealing temperature, wherein the first annealing temperature is between approximately 439C and approximately 451C" are thus non-limiting.

In regards to claim 2, Bryan further discloses the sum of the first quantity of the first ionic material (10¹⁴ atoms/cm²) and the second quantity of the second ionic material (10¹⁴ atoms/cm²) is no greater than approximately 2x10¹⁶ cm⁻².

In regards to claim 6, Bryan further discloses the second ionic material comprises hydrogen ions to react with the device layer at an energy level of approximately 40 KeV (col. 4, lines 57-59).

5. Claim 7 is objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Steven Loke whose telephone number is (571) 272-1657. The examiner can normally be reached on 8:20 am to 5:50 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie Lee can be reached on (571) 272-1732. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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sl June 5, 2005 Steven Loke Primary Examiner